

Photoresist Product Road Map: Overview

Next Generation Lithography

FEP-100

Positive resists
for EBDW

FEN-100

Negative resists
for EBDW



ArF (193nm) DUV Lithography

High Resolution ArF

GAR-9000

For Immersion
Lithography

GAR-8000 Series

ArF Single layer

GAR-7000 Series

KrF (248nm) DUV Lithography

GKR-6000 Series

High Resolution
Resists
for Dense & Iso lines

GKR-5000 Series

High Resolution
Resists
for CH with HT PSM

GKR-3000

for CH
for Dense & Iso
lines

GKR-4000

for thick film ion implant



Lithography Node (nm)



Product Descriptions

248 nm Single Layer

GKR 6757F *Sub 150nm Applications*
GKR 5317V3 *Advanced Contact Hole Resist*
GKR 4602PP *Thick Film Resist*
GKR 5303 *200 nm Contact Hole*
GKR 3424PP *250 nm Multi-Purpose Resist*

193 nm Single Layer

GAR-8105G1 *90nm Dense Lines*
GAR-7307Y2 *120nm Contact Holes*
GAR-8205B15 *Multi-Purpose*

For additional product line technical information:

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